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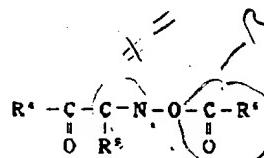
(54) PHOTORESISTIVE POLYIMIDE PRECURSOR COMPOSITION FOR I-LINE

(57) Abstract:

PURPOSE: To obtain a high-sensitivity photosensitive polyimide precursor composition without using a sensitizer, to facilitate production, to attain excellent performance as a negative type and a positive type and to improve the physical film property after imidation by incorporating specified polymer, compd. and oxime compd.



CONSTITUTION: A polymer with a structural unit shown by formula I as the main component, a compd. having an ethylenic unsaturated double bond and an oxime compd. shown by formula II are incorporated. In formula I, R1 is a 3 or 4-valence org. group having at least two carbon atoms, R2 is a bivalent org. group having at least two carbon atoms, R3 is hydrogen, alkali metal ion, etc., and (n) is 1 or 2. In formula II, R4 is 1-10C alkyls, 5-10C cycloalkyls, etc., R5 is hydrogen atom, 1-10C alkyls, etc., and R6 is 1-10C alkyls, 1-10C alkoxy, etc.



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